

NOVEL HAFNIUM-CONTAINING COMPOUND, HAFNIUM PRECURSOR
COMPOSITION CONTAINING SAME, HAFNIUM-CONTAINING THIN FILM
USING HAFNIUM PRECURSOR COMPOSITION, AND PREPARATION METHOD
THEREFOR

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ABSTRACT

The present invention relates to a hafnium-containing precursor that can be used in the formation of various hafnium-
10 containing thin films, wherein the hafnium-containing precursor is liquid at room temperature and exhibits high volatility and high thermal stability and thus can be used in a high-quality hafnium-containing thin film and a preparation method therefor.

15 (Fig. 6)